ABSTRACT

In the exposure method which carries out optical proximity correction processing for exposure data having a plurality of exposure patterns and exposes a sample in accordance with such corrected exposure data, the exposure patterns to be corrected are converted, in the optical proximity correction processing, into a minus objective pattern and a minus pattern to be deleted from the minus objective pattern, to form corrected exposure data. And, the minus pattern is deleted from the minus objective pattern of the corrected exposure data to bitmap a corrected exposure pattern, to expose a sample in accordance with such bitmapped corrected exposure pattern.